



TCAD+APSO SIMULATIONS FOR CLICTD

Katharina Dort

Vertex and Tracker Meeting

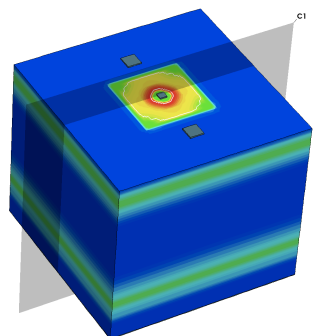
18/01/2021



- Simulation studies for monolithic CMOS sensors are crucial to optimise sensor design in view of e.g.:
 - Small capacitance
 - Fast charge collection
- Optimised sensors can be **evaluated** by **combining electrostatic TCAD and transient Monte Carlo simulations**
 - Less computing intensive than transient TCAD
 - Can save time/costs compared to fabricating prototypes and evaluating them in beam tests

See previous talk by Magdalena

→ Complementary approaches that can give a full picture of a sensor when combined



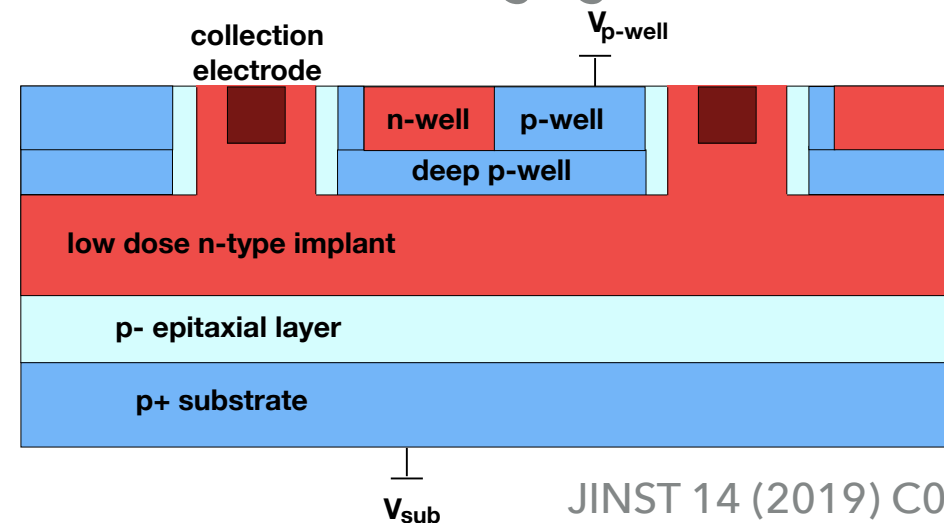
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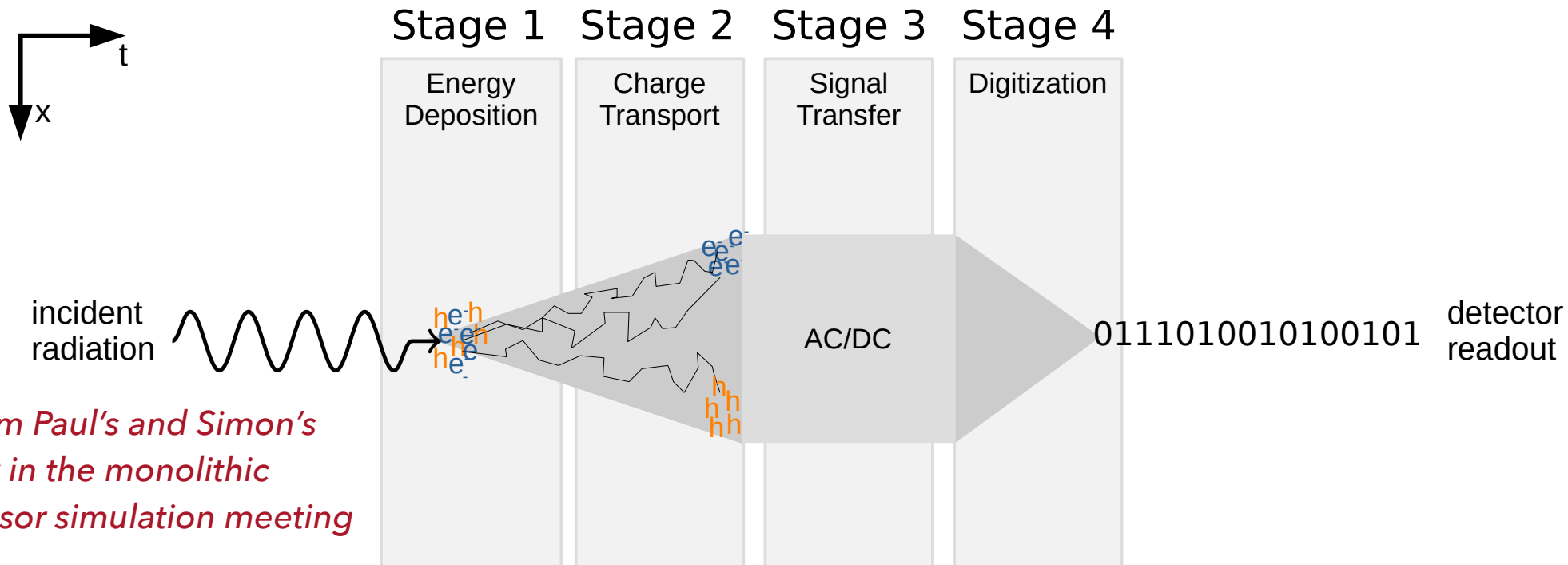
Simulating monolithic CMOS sensors with small collection diode

- Complex non-uniform electric field in the small collection diode design
- Knowledge from standard planar sensors does not necessarily hold -> **simulations needed to design and evaluate new sensor concepts**
- In this talk:

180 nm CMOS imaging sensor CLICTD



JINST 14 (2019) C05013



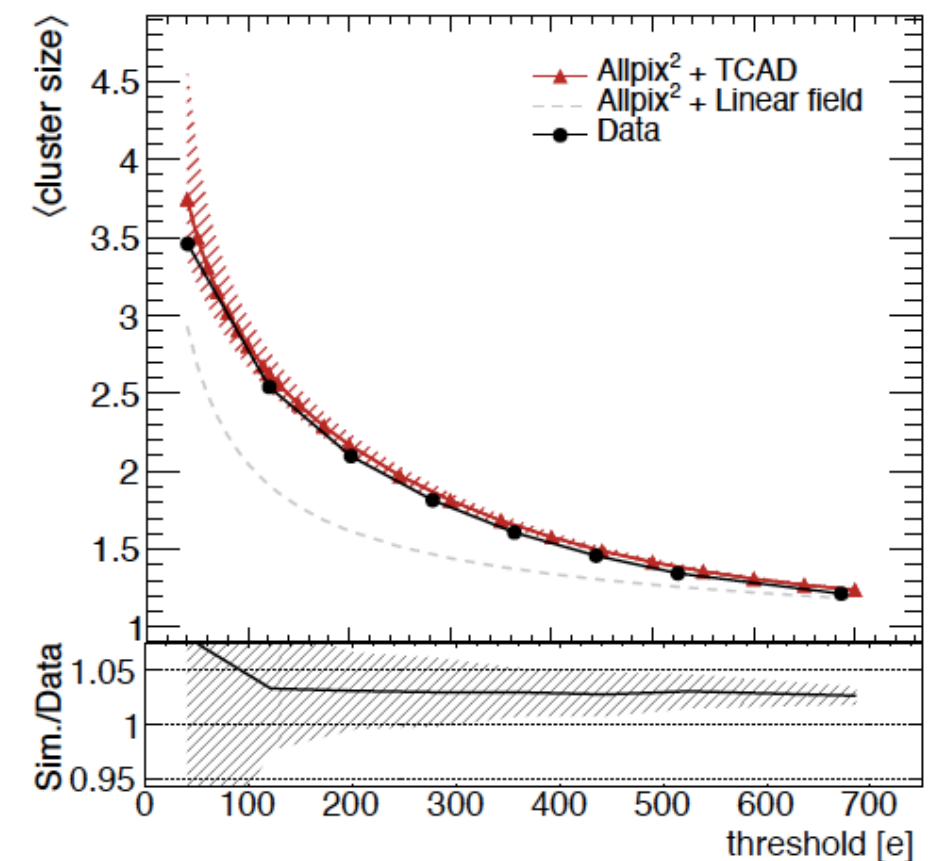
<https://cern.ch/allpix-squared/>

NIM A 901 (2018) 164-172

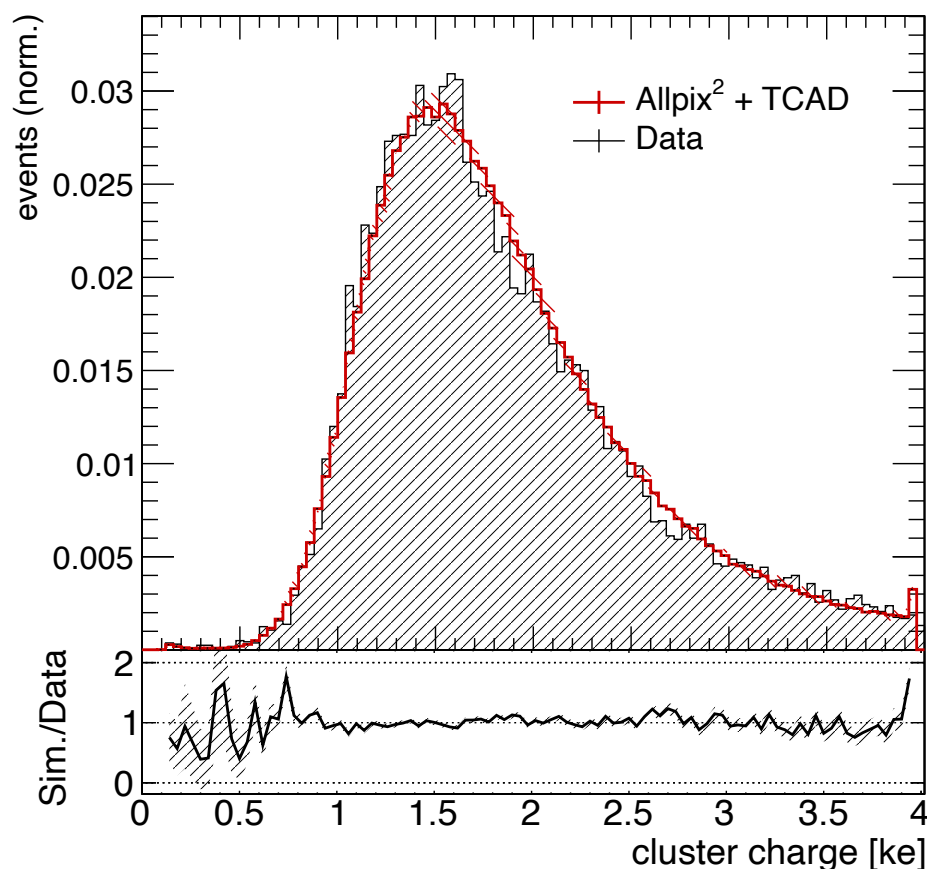
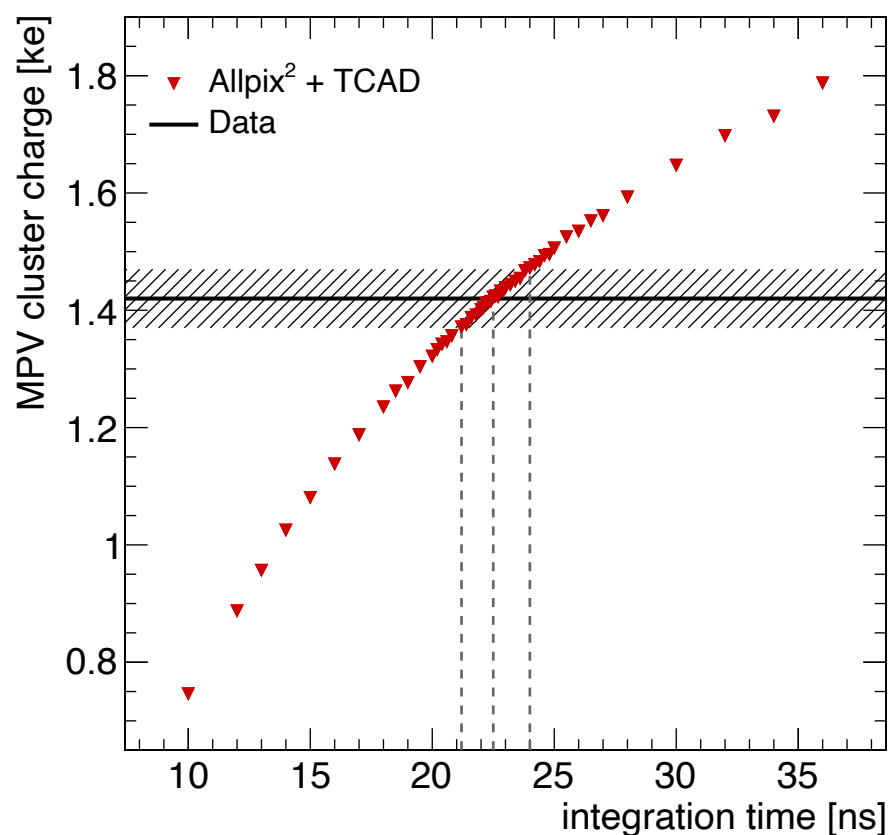
Please see e.g. <https://indico.cern.ch/event/984049/>

- Allpix Squared handles all simulation steps from charge deposition in sensor to digitisation of signal
- Static fields are imported from 3D TCAD simulations to ensure precise field modelling
All 3D TCAD simulations in this talk were performed by M. Munker
- Validation of simulation with Investigator test-chip (developed within ALICE ITS upgrade)

NIM A 964 (2020) 163784



- Integration time = time within which charge carriers are propagated in the sensor
- Integration time is linked to sensor design -> emulates effective recombination time of charge carriers
- Chosen such that most probable cluster charge value matches with data
- Implementation of charge carrier lifetime model would avoid the tuning procedure for the integration time parameter



- Charge carrier recombination was implemented based on the following models:

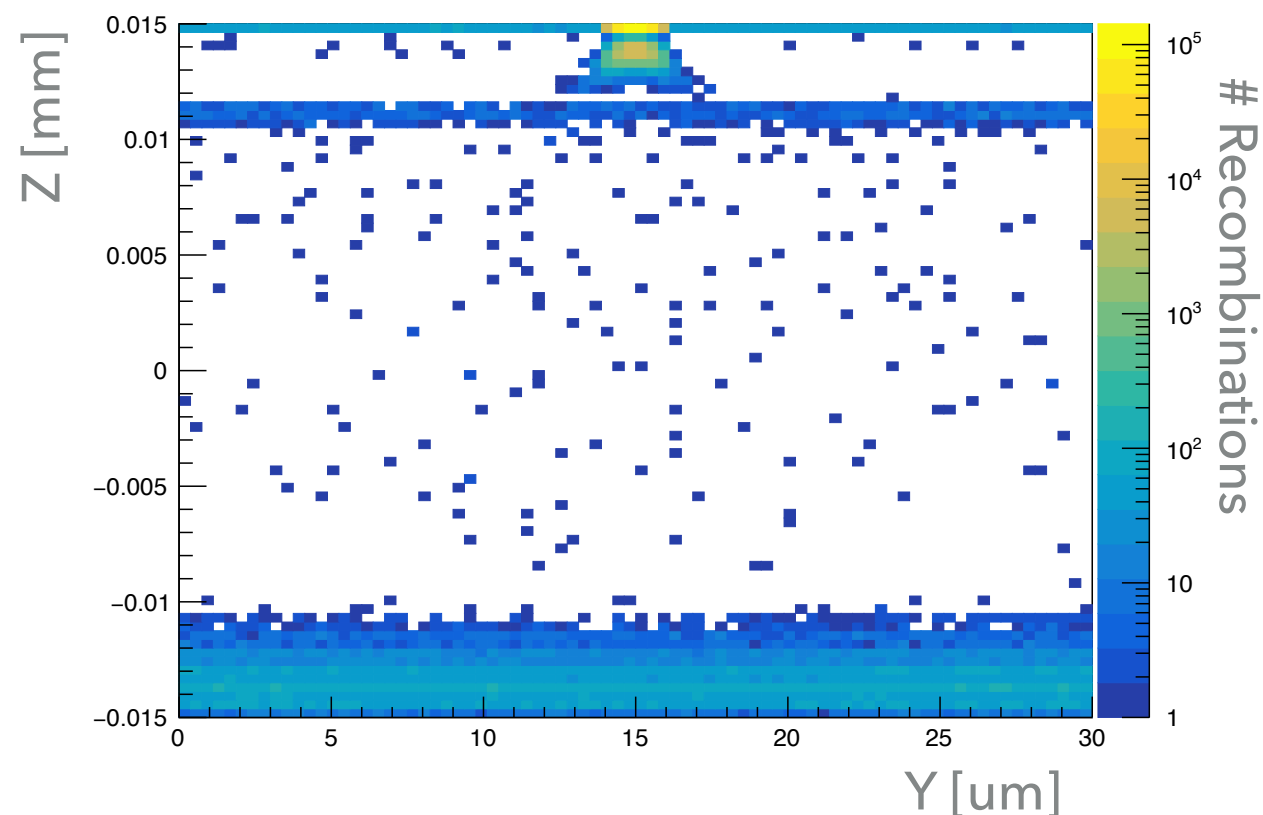
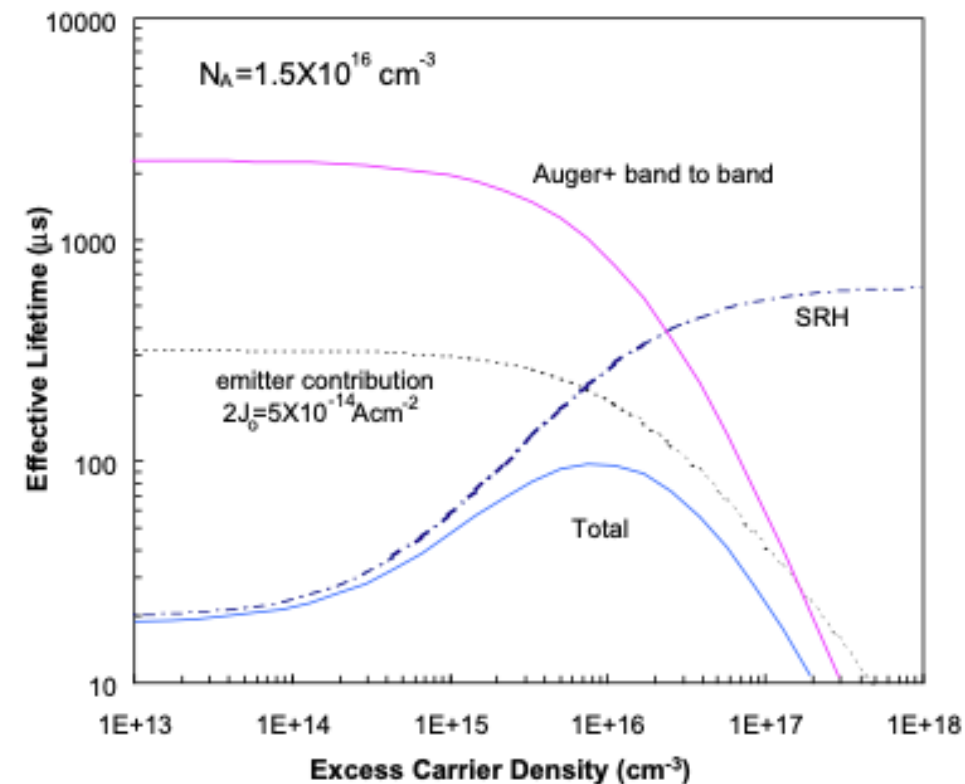
- Shockley-Read-Hall (SRH) recombination (doping-dependent)
- Auger recombination (doping-dependent)

- Effective charge carrier lifetime:

$$\frac{1}{\tau_{eff}} = \frac{1}{\tau_{SRH}} + \frac{1}{\tau_{Auger}}$$

- Effective lifetime in highly doped bulk : a few nanoseconds

Solar Energy 76 (2004) 255-262



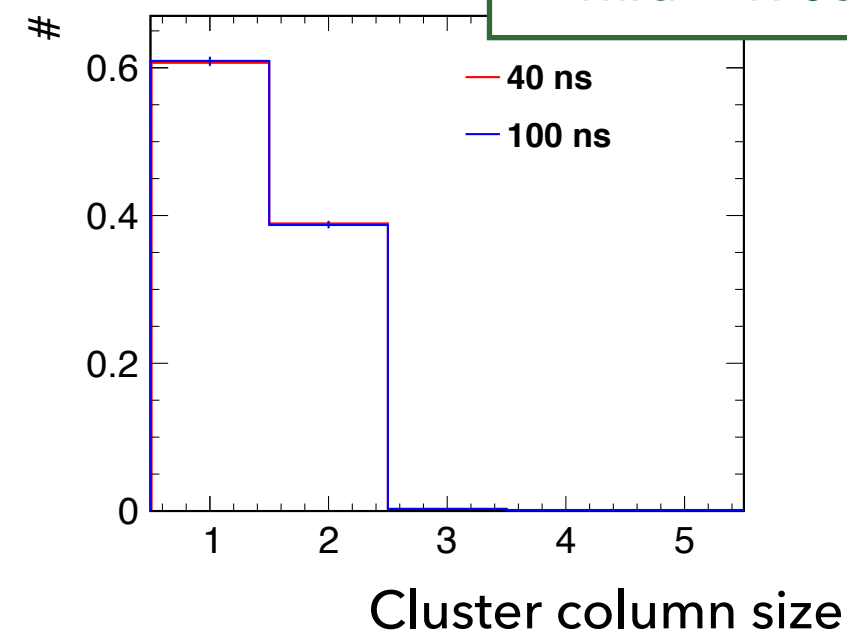
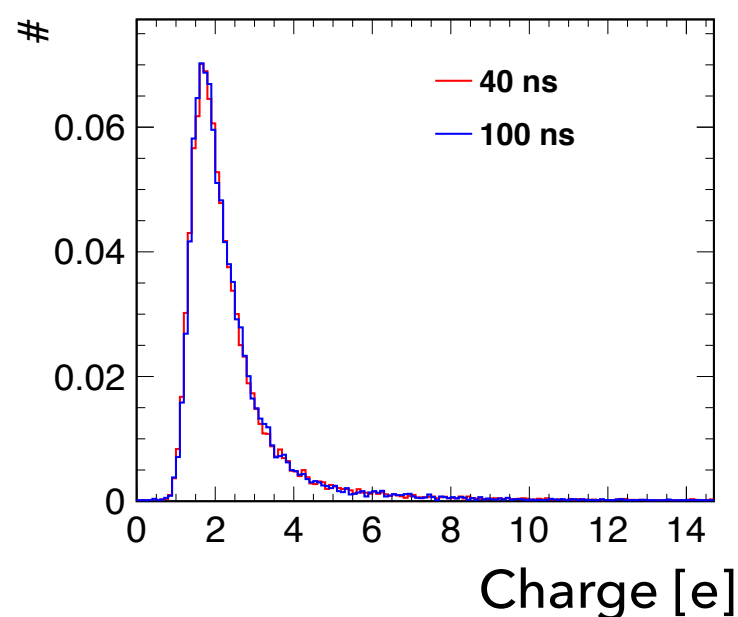
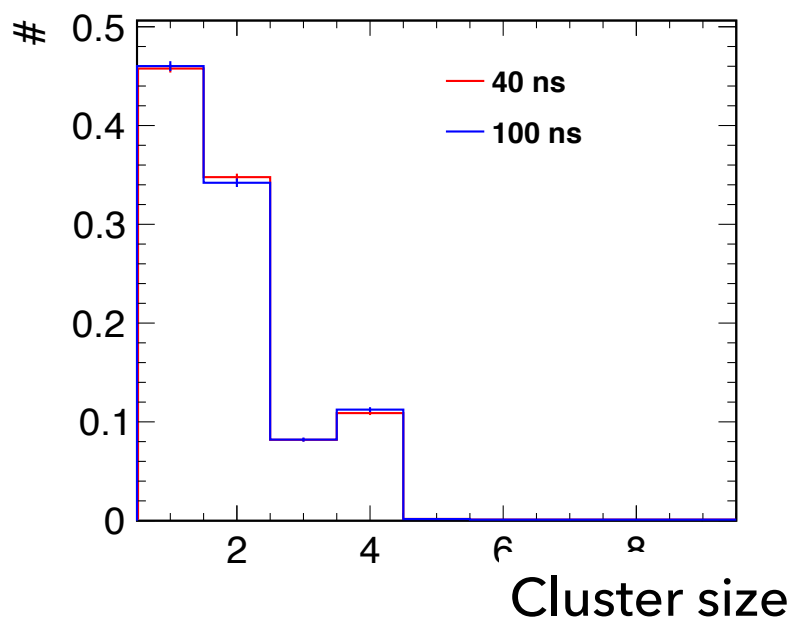
Simulation set-up

- 5.4 GeV electron beam incident on simulated CLICTD sensor (30 um epitaxial layer + 20 um substrate)
- No simulation of full telescope set-up
- Doping profile, weighting potential and electrostatic field maps are imported from 3D TCAD simulation
- Simulations only for -6V/-6V bias voltage at p-wells/substrate
- Simulations only for pixel flavour with continuous n-implant

- Cluster observables not sensitive to changes of integration time within reasonable range

$$C_a = 2 \times 10^{-30} \text{cm}^6/\text{s}$$

$$\text{Thrd} = 170e$$



AUGER RECOMBINATION MODEL

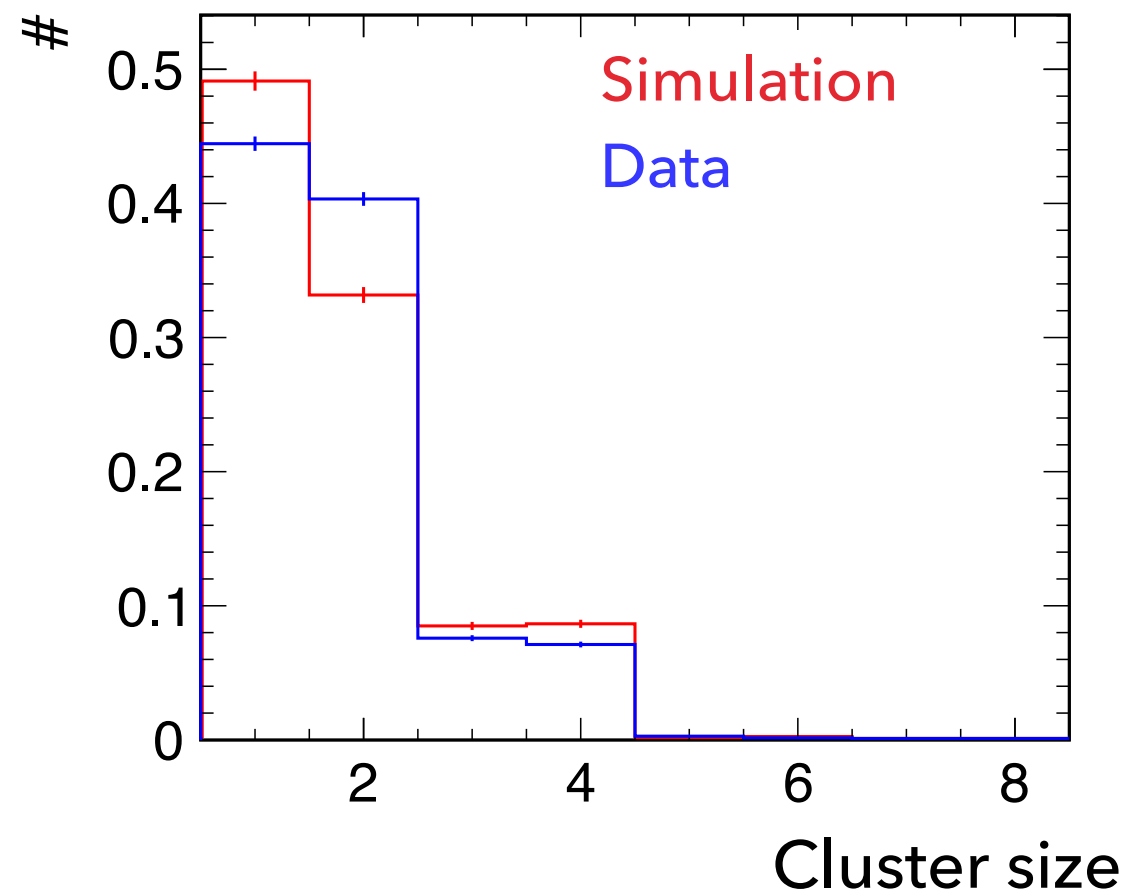
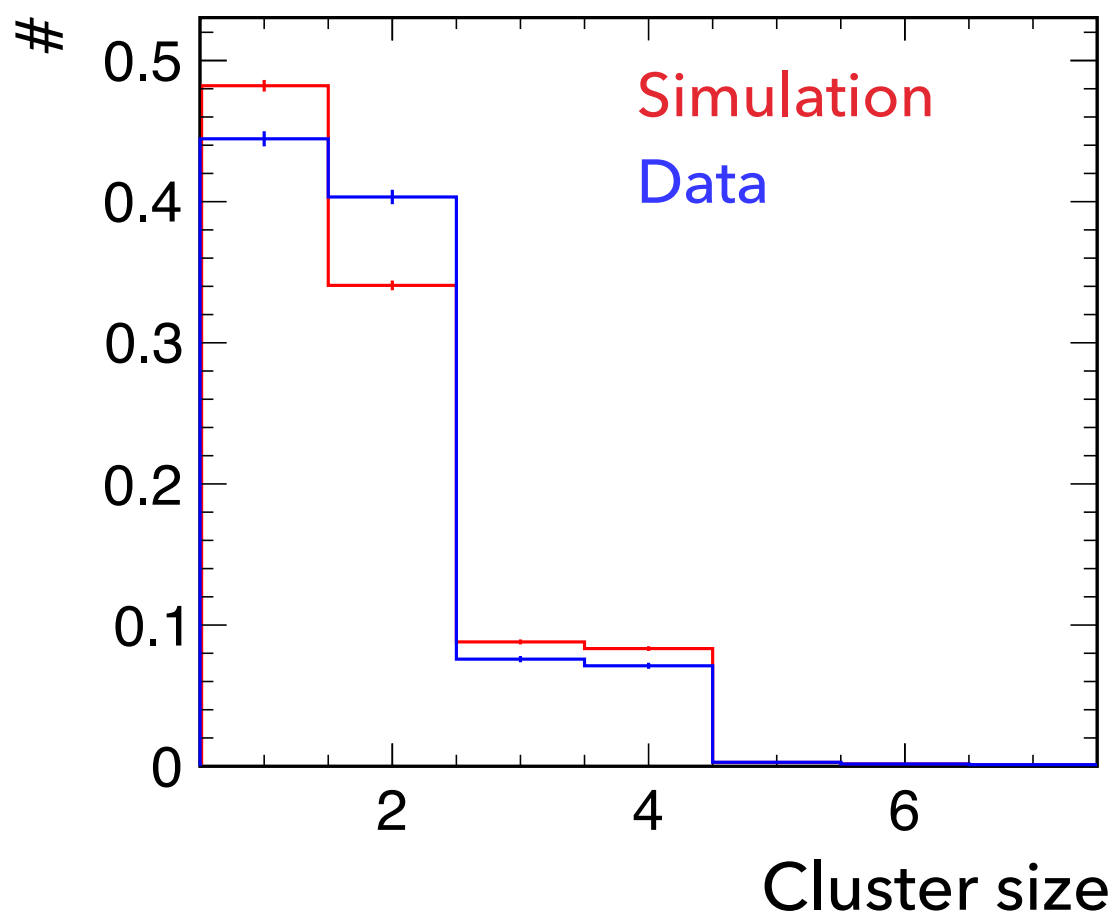
How sensitive are cluster observables to variations of the parameters in the lifetime models?

Thrd = 170e

- Lifetime for Auger recombination: $\tau_{Auger} = \frac{1}{C_a \cdot n^2}$
- Increasing Auger coefficient is expected to lead to a **lower effective lifetime** and therefore a **decrease in cluster size**
- Minor impact on cluster size at a threshold of 170e

$$C_a = 2 \times 10^{-30} \text{cm}^6/\text{s}$$

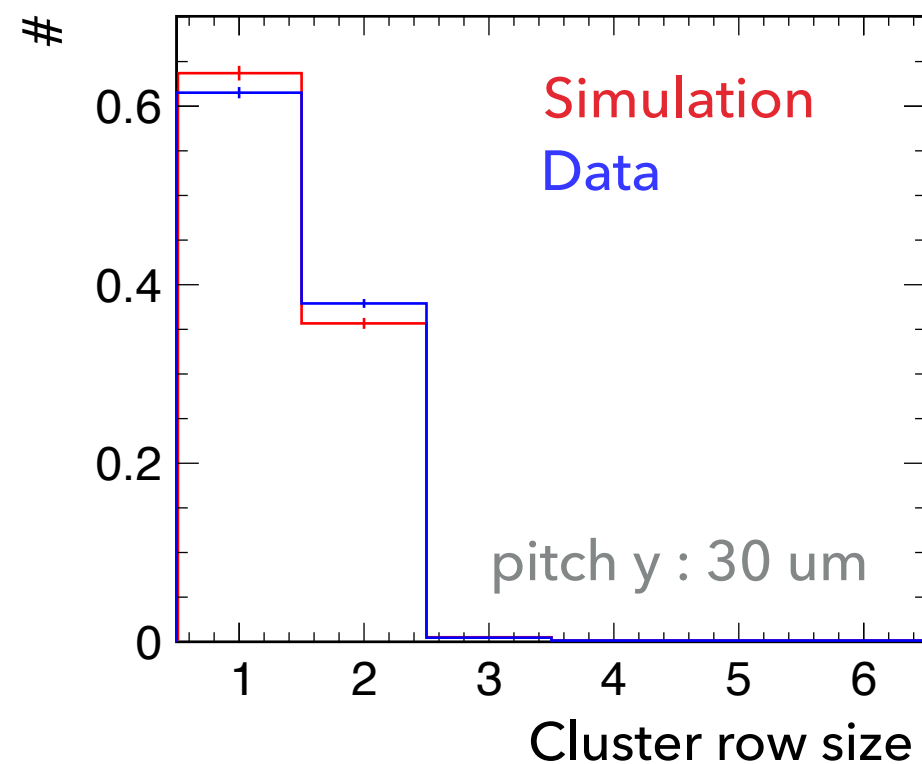
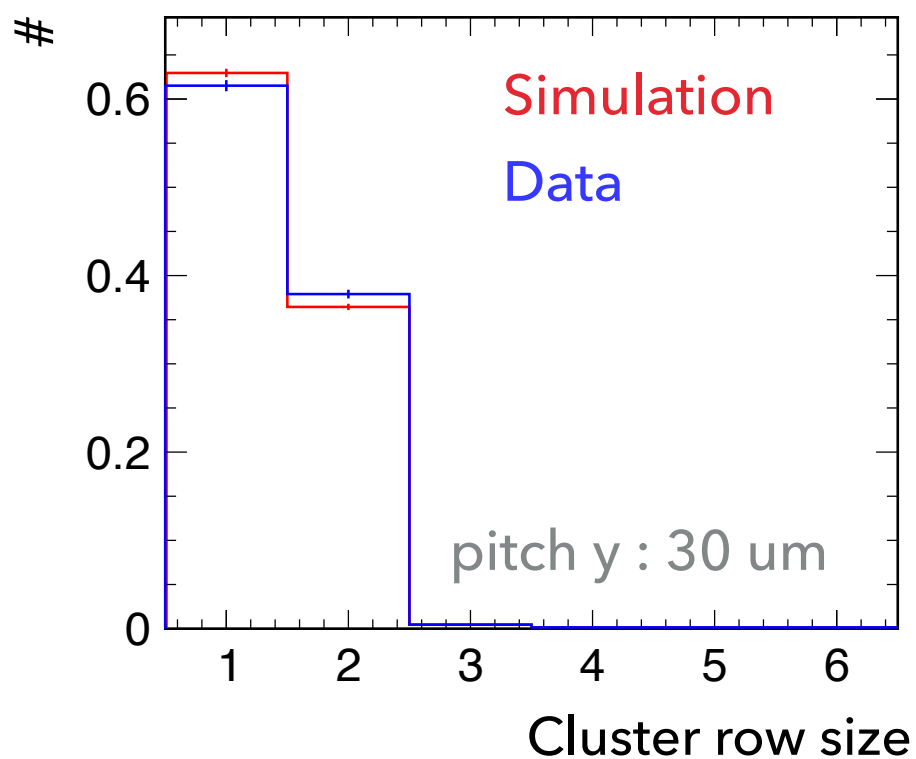
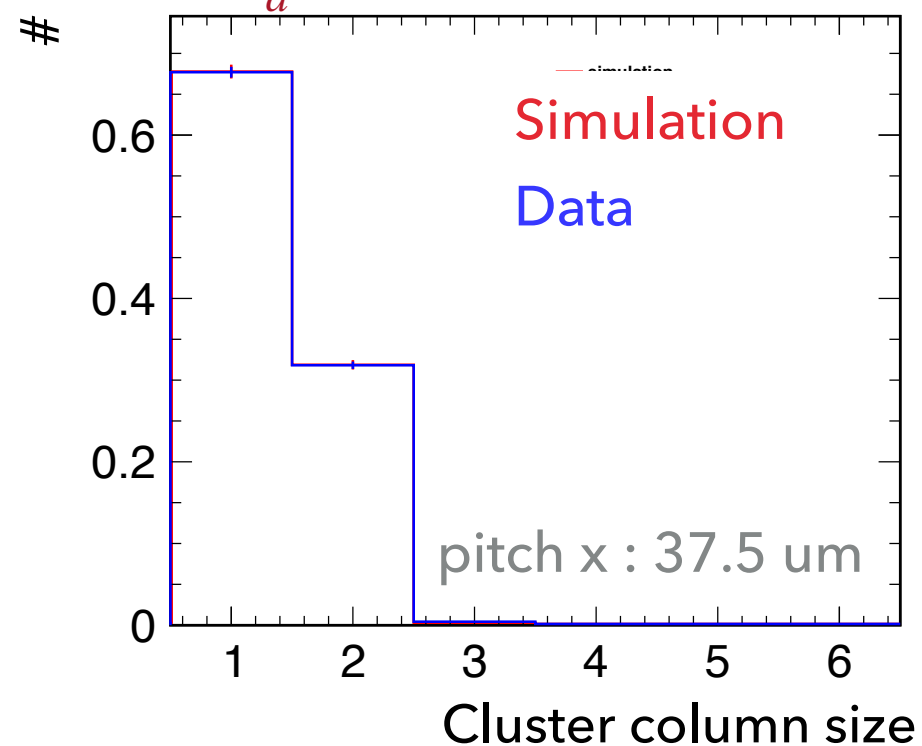
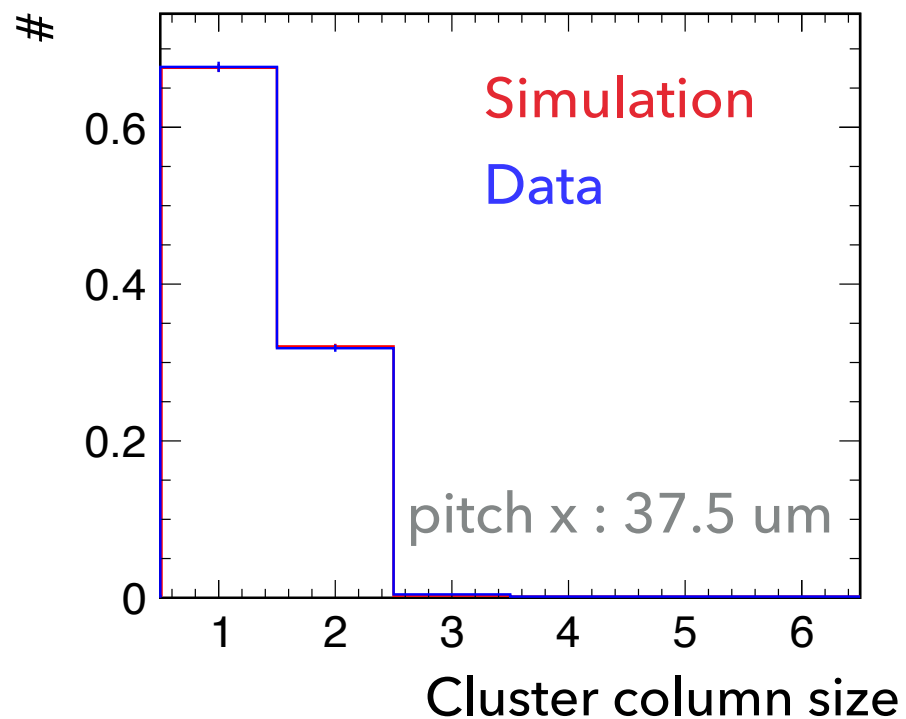
$$C_a = 4 \times 10^{-30} \text{cm}^6/\text{s}$$



AUGER RECOMBINATION MODEL

$$C_a = 2 \times 10^{-30} \text{ cm}^6/\text{s}$$

$$C_a = 4 \times 10^{-30} \text{ cm}^6/\text{s}$$



- Cluster size in row direction more sensitive to variations in Auger coefficient due to smaller pixel pitch

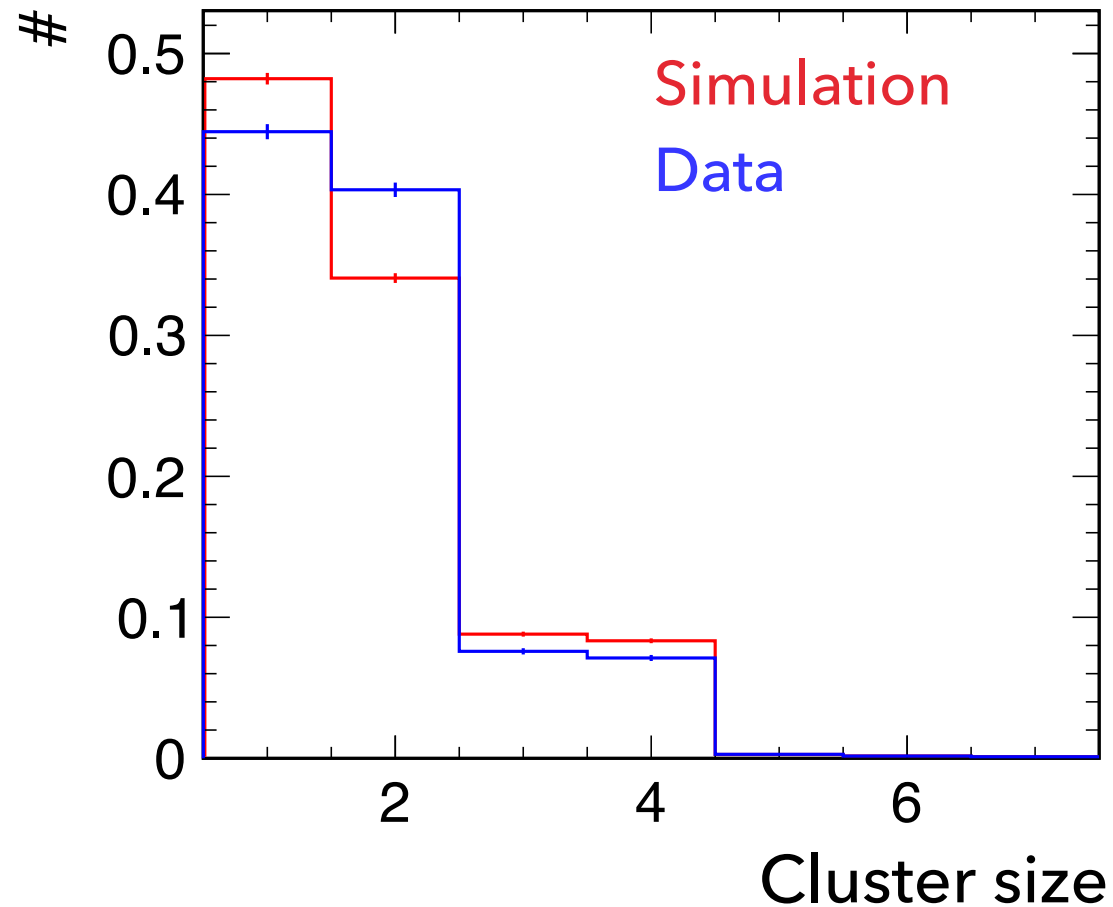
DETECTION THRESHOLD

Could uncertainty in threshold calibration account for differences between data and simulation?

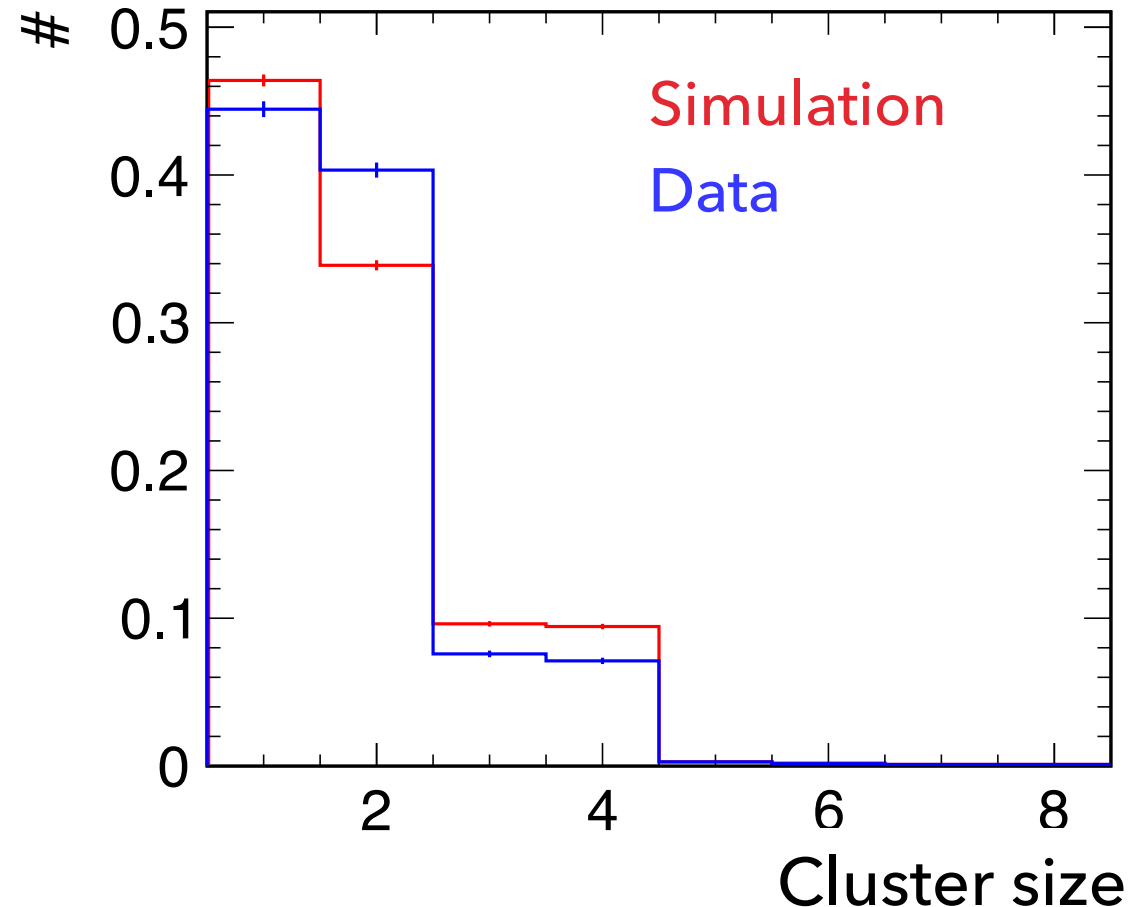
$$C_a = 2 \times 10^{-30} \text{cm}^6/\text{s}$$

- Threshold is varied by 20 e which is significantly higher than the threshold uncertainty in data (< 10 e)

Threshold = 170 e



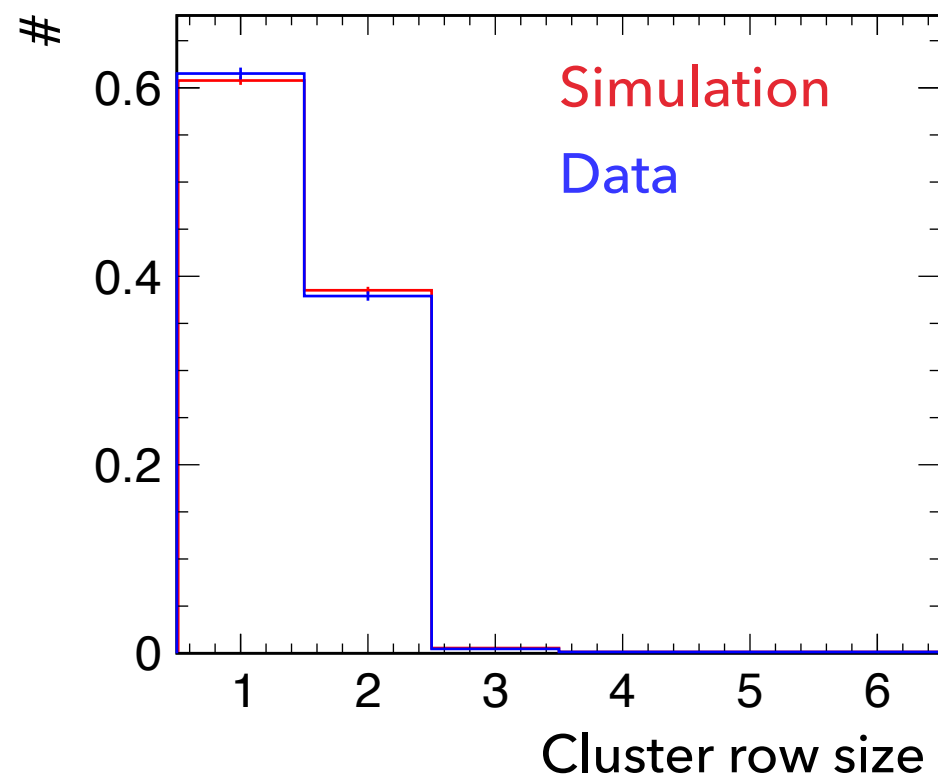
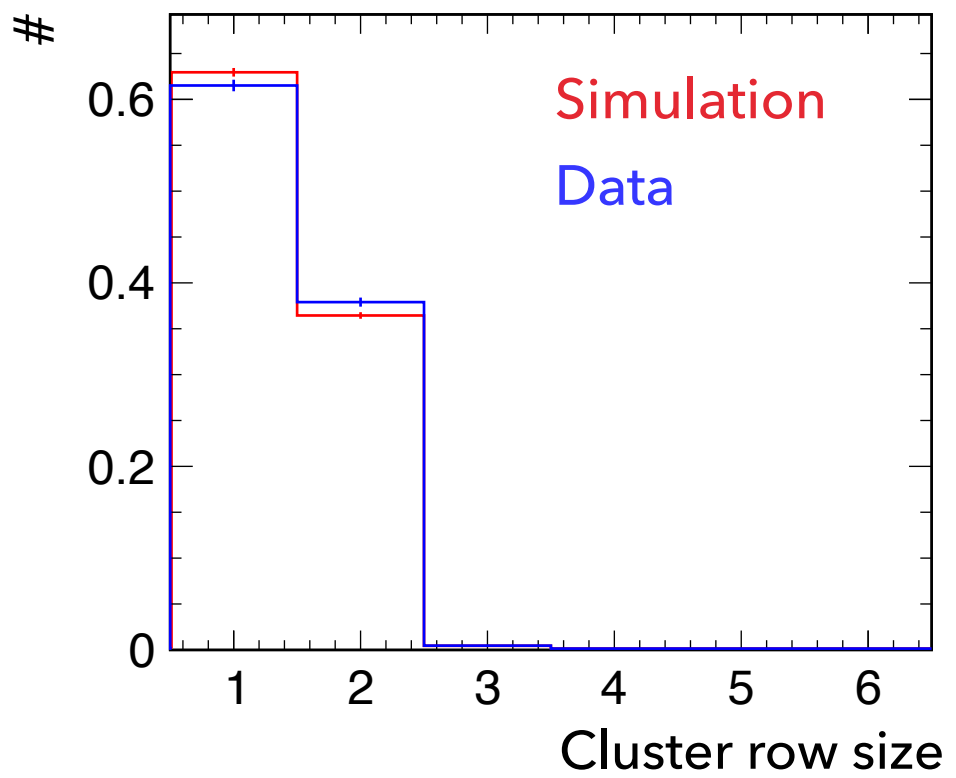
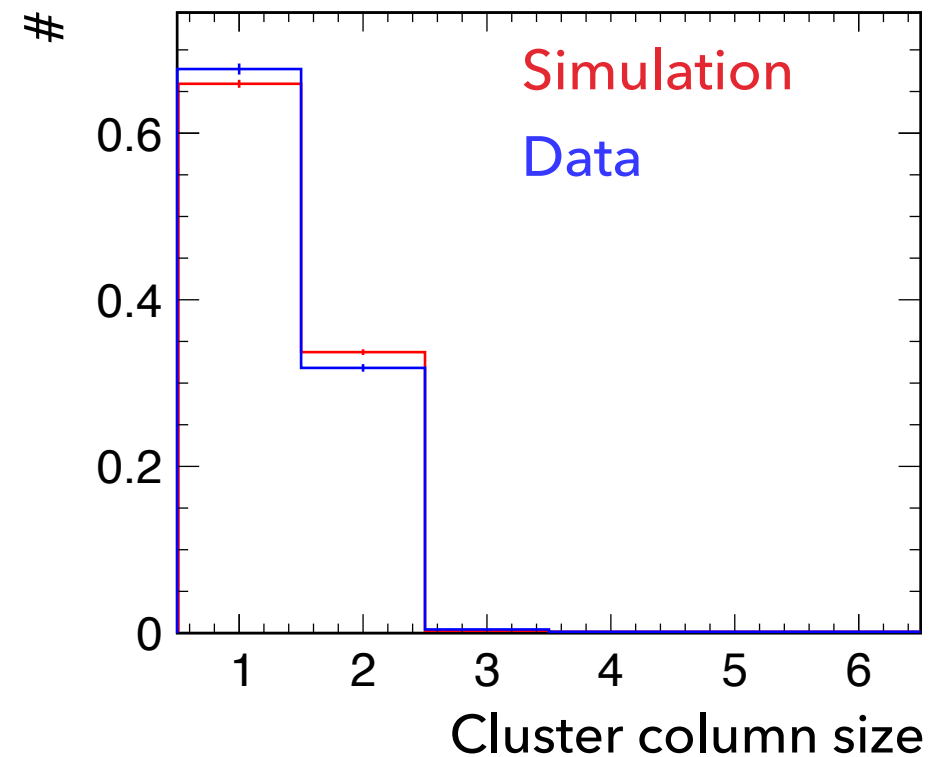
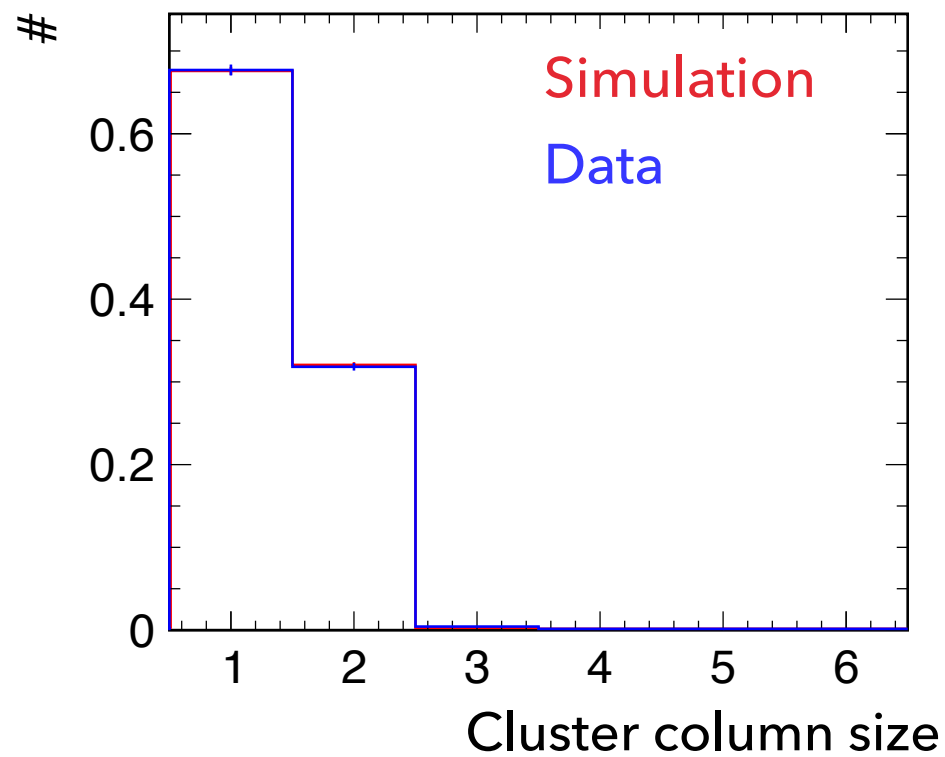
Threshold = 150 e



DETECTION THRESHOLD

Threshold = 170 e

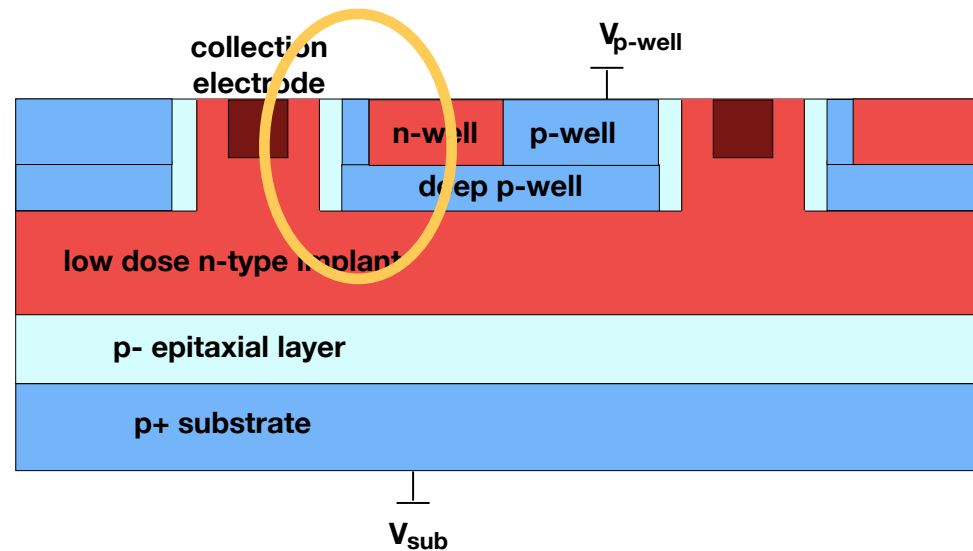
Threshold = 150 e



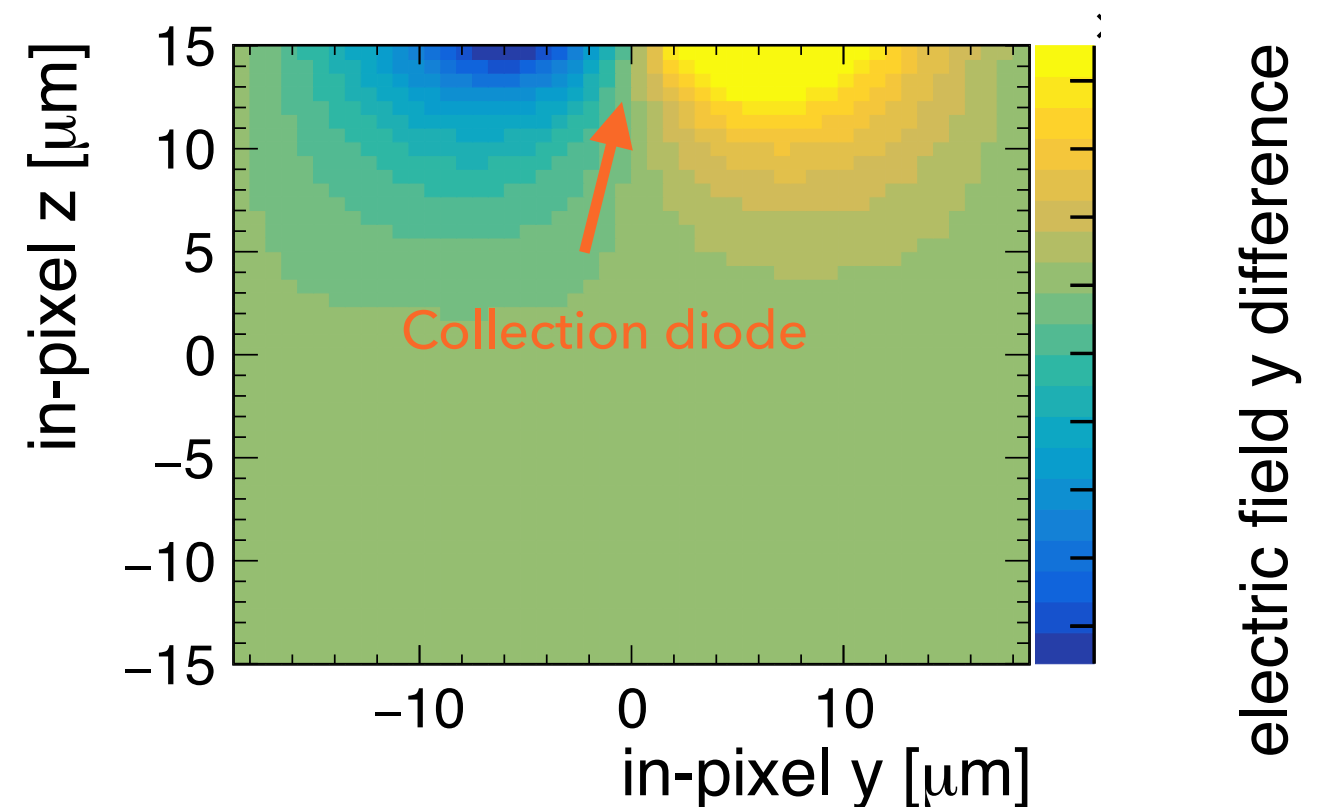
LATERAL PROFILE SPREAD OF P-WELL IMPLANT

What is the impact of uncertainties in the doping profiles on the charge sharing ?

- Lateral spread of the profile at the edge of the p-well implant (*p-well smearing*) was varied
- Low smearing leads to a **stronger lateral electric field**



Differences in electric field in y
Low p-well smearing - high p-well smearing



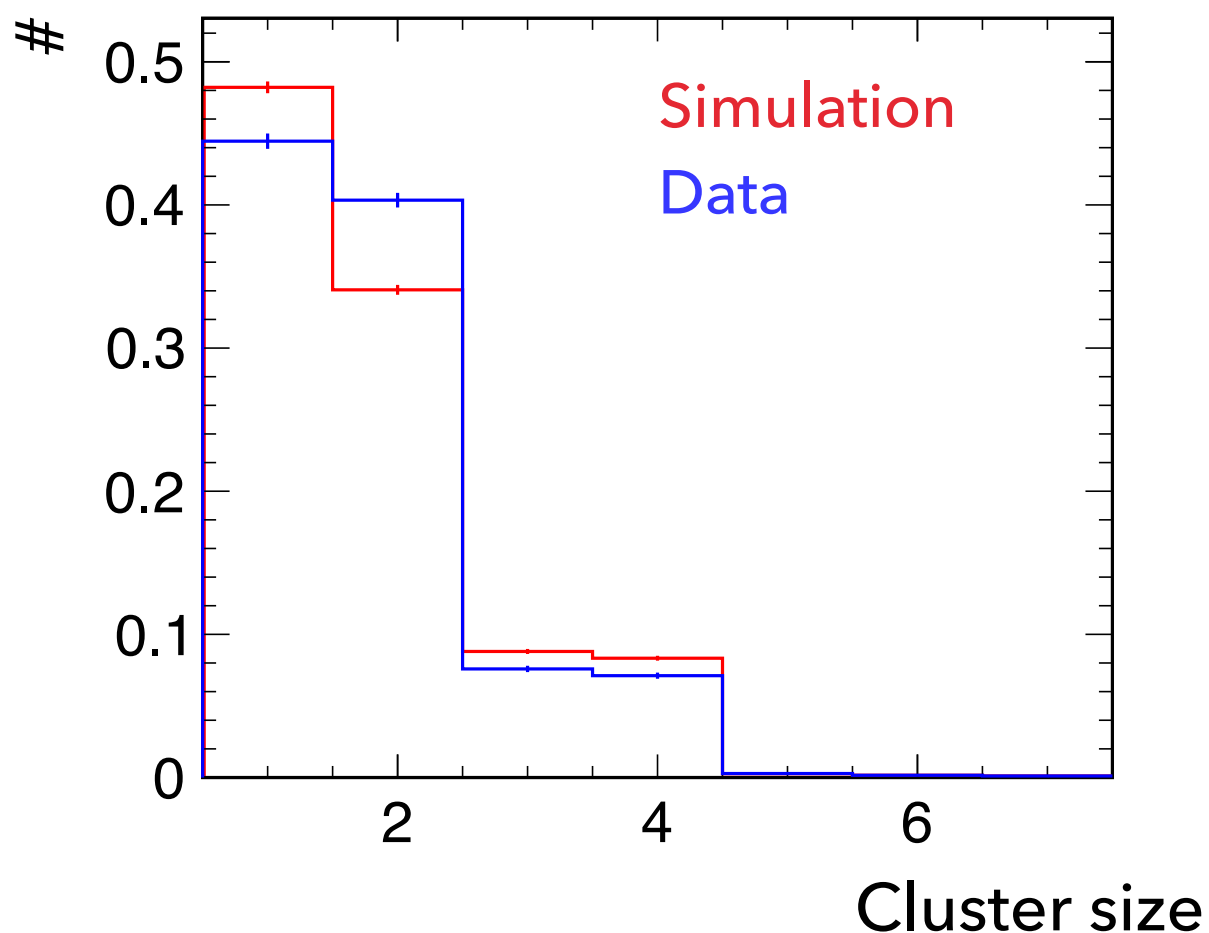
P-WELL SMEARING

- Stronger lateral field leads to **less charge sharing** and consequently a **lower cluster size**
- Ignorance of exact doping profiles has considerable impact on cluster observables
- Tuning the doping profiles (within the given uncertainties) to the data is **not** the objective of this study

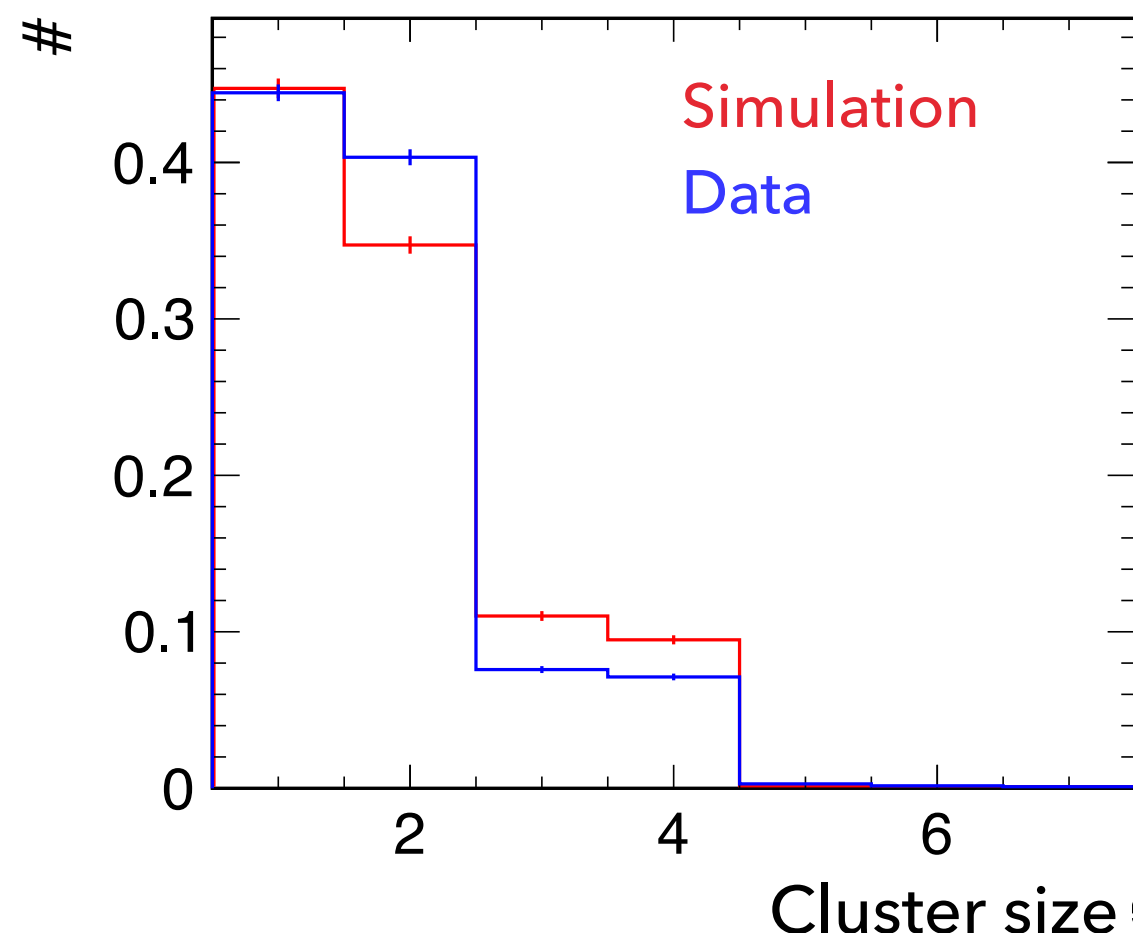
$$C_a = 2 \times 10^{-30} \text{cm}^6/\text{s}$$

$$\text{Thrd} = 170e$$

Low p-well smearing

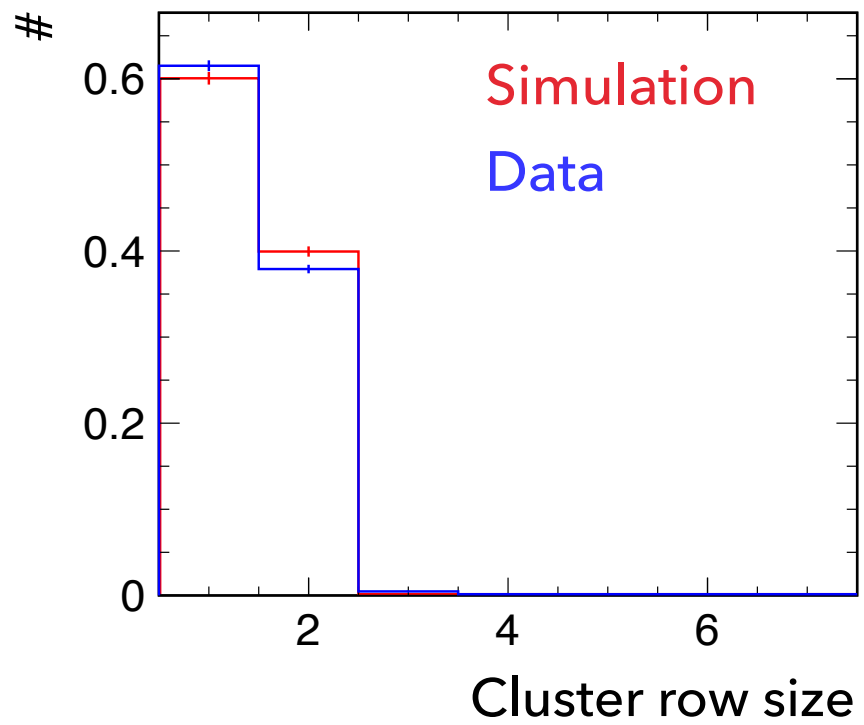
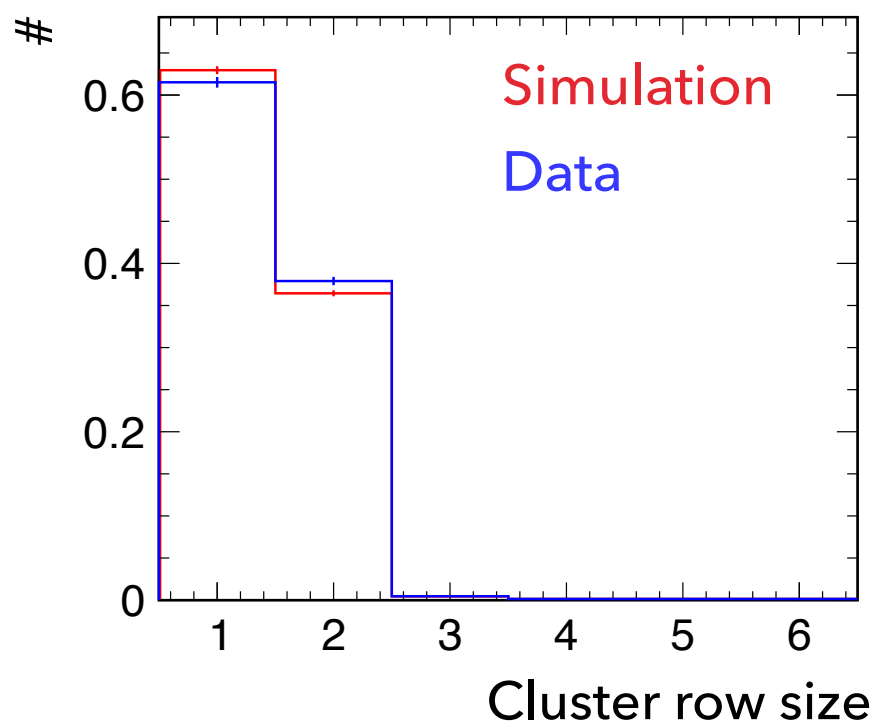
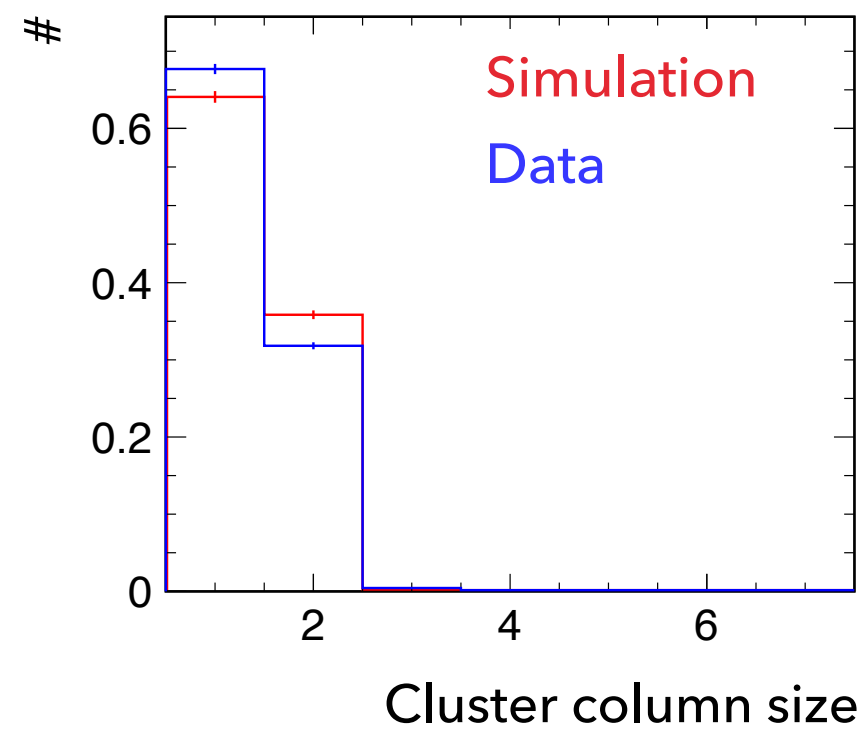
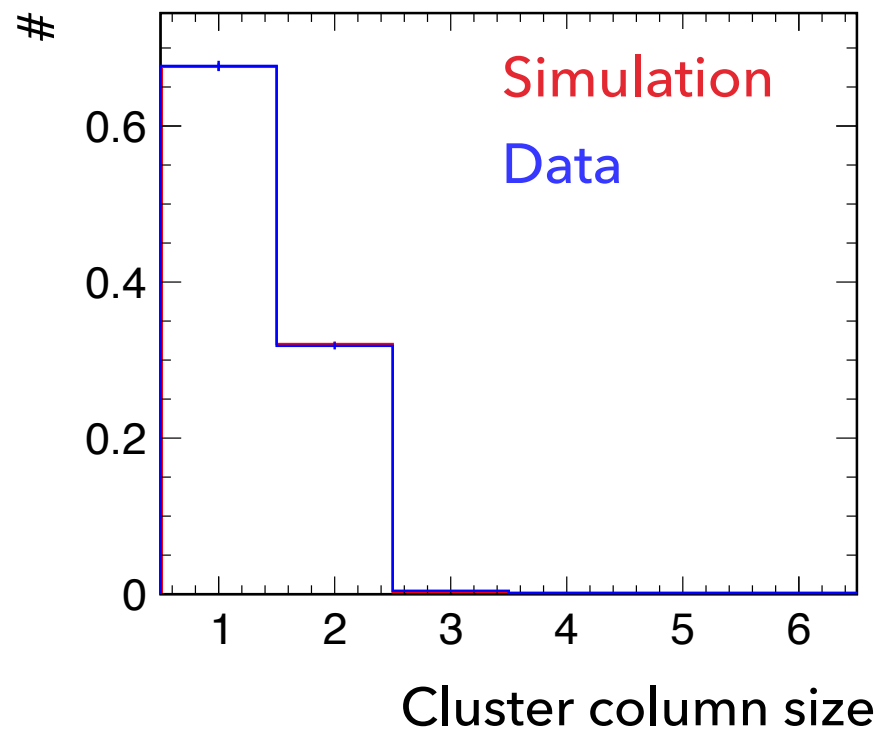


High p-well smearing



Low p-well smearing

High p-well smearing

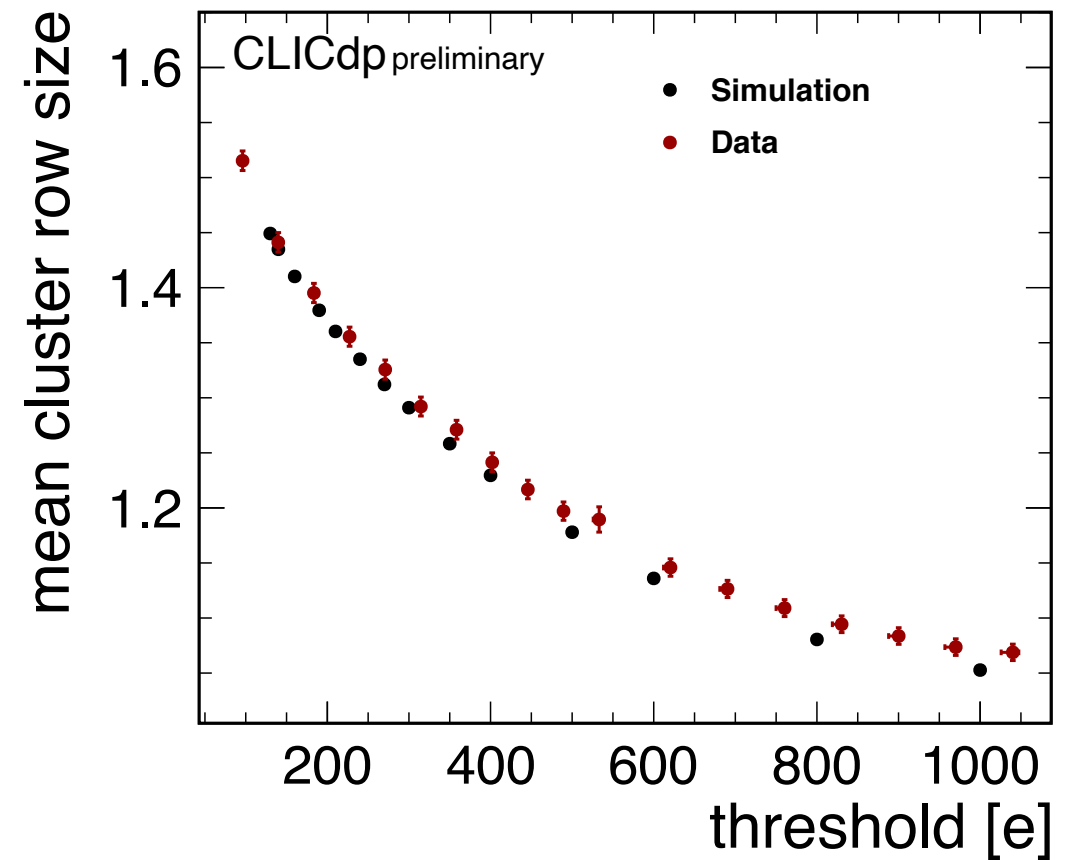
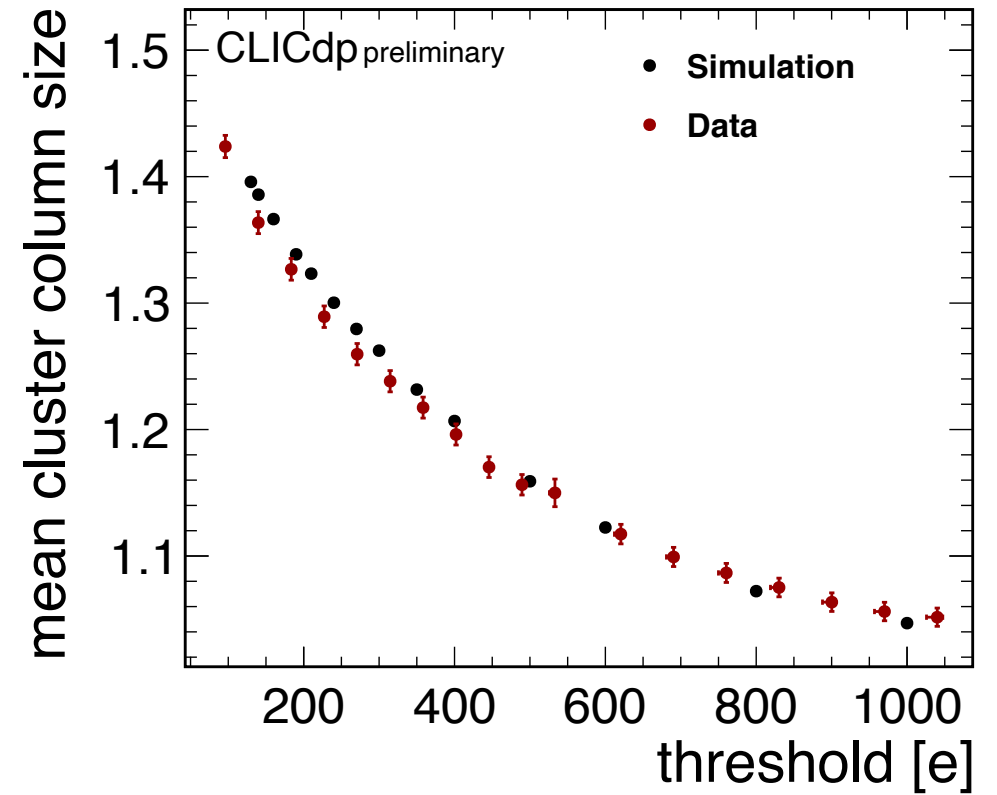
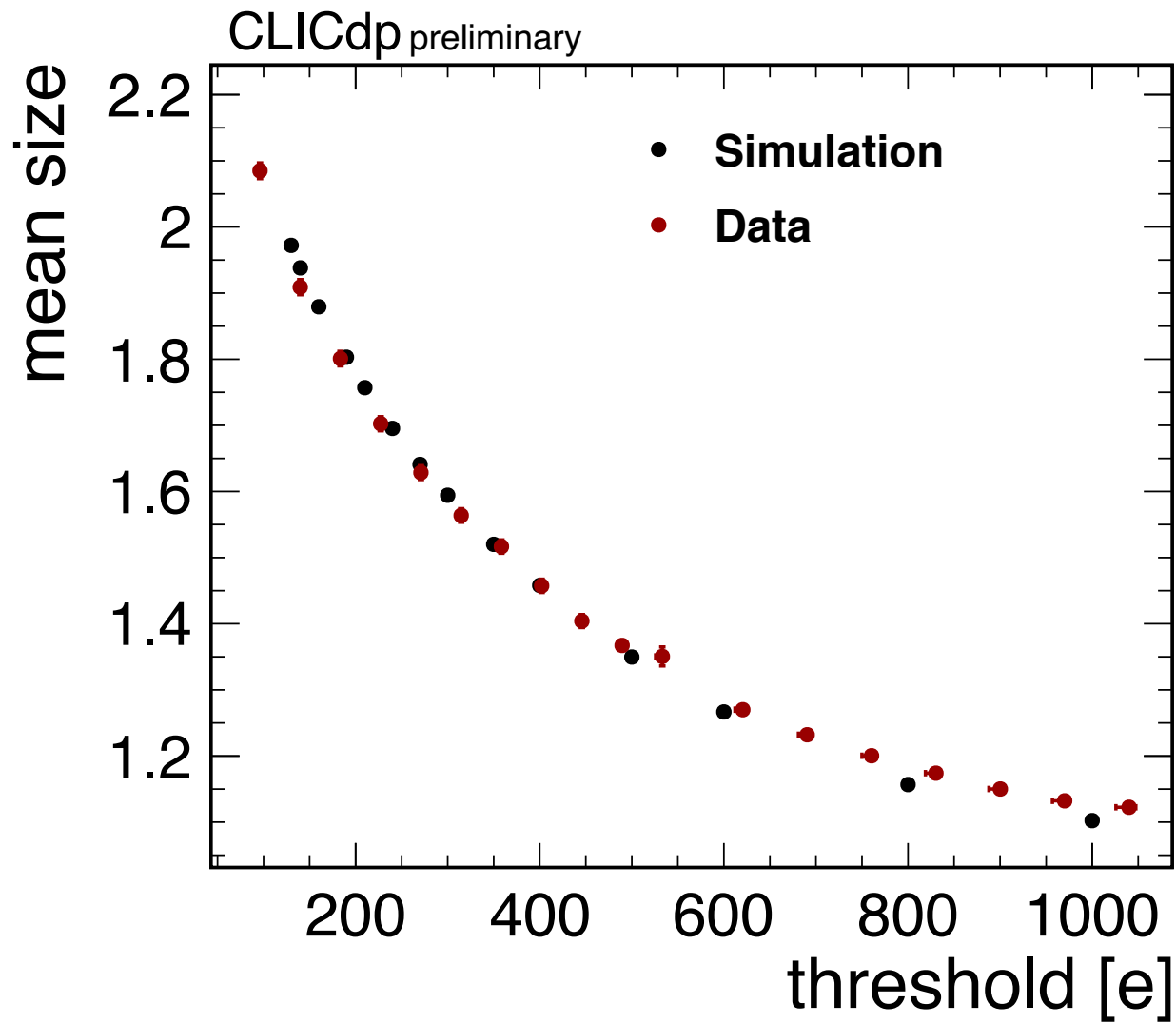


- Effect of p-well smearing is clearly visible in both spatial dimensions

High smearing
 $C_a = 2 \times 10^{-30} \text{cm}^6/\text{s}$

Threshold scan

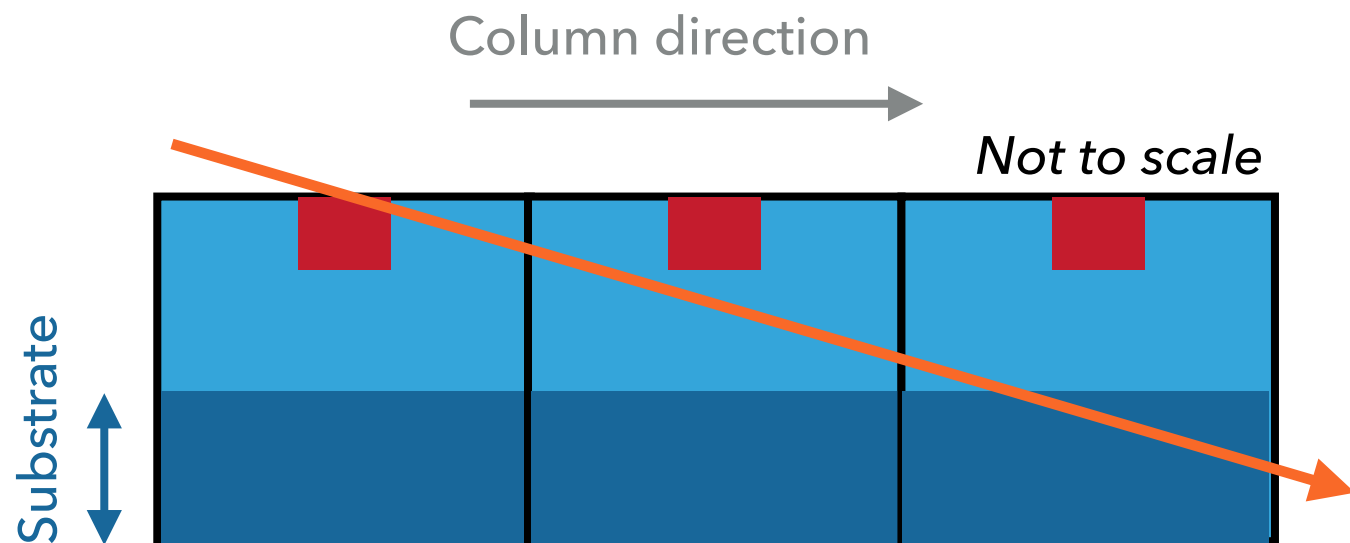
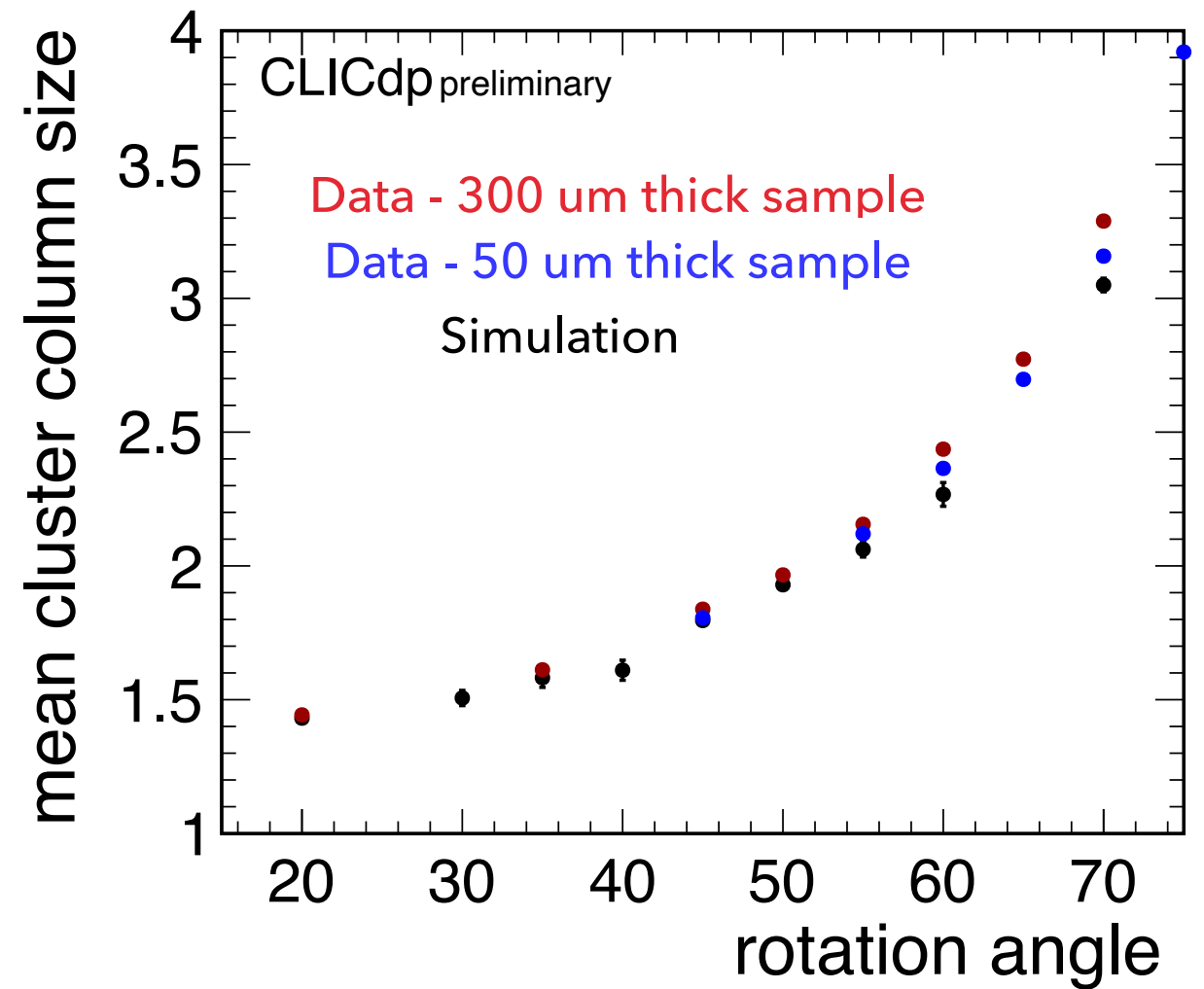
- Agreement between data and simulation does not deteriorate with increasing threshold



High smearing
 $C_a = 2 \times 10^{-30} \text{cm}^6/\text{s}$
 Thrd = 170e

Rotation scan

- Sensor is tilted in column direction
- Charge carriers created **in or close to the substrate** are expected to have a **stronger contribution to the cluster size for increasing rotation angles**



Summary

- **Charge carrier recombination models** (Shockley-Read-Hall and Auger recombination) have been implemented
 - Effective charge carrier lifetime is determined by these models and **not by integration time**
- **Ignorance of exact doping profiles** introduces uncertainties in the simulation

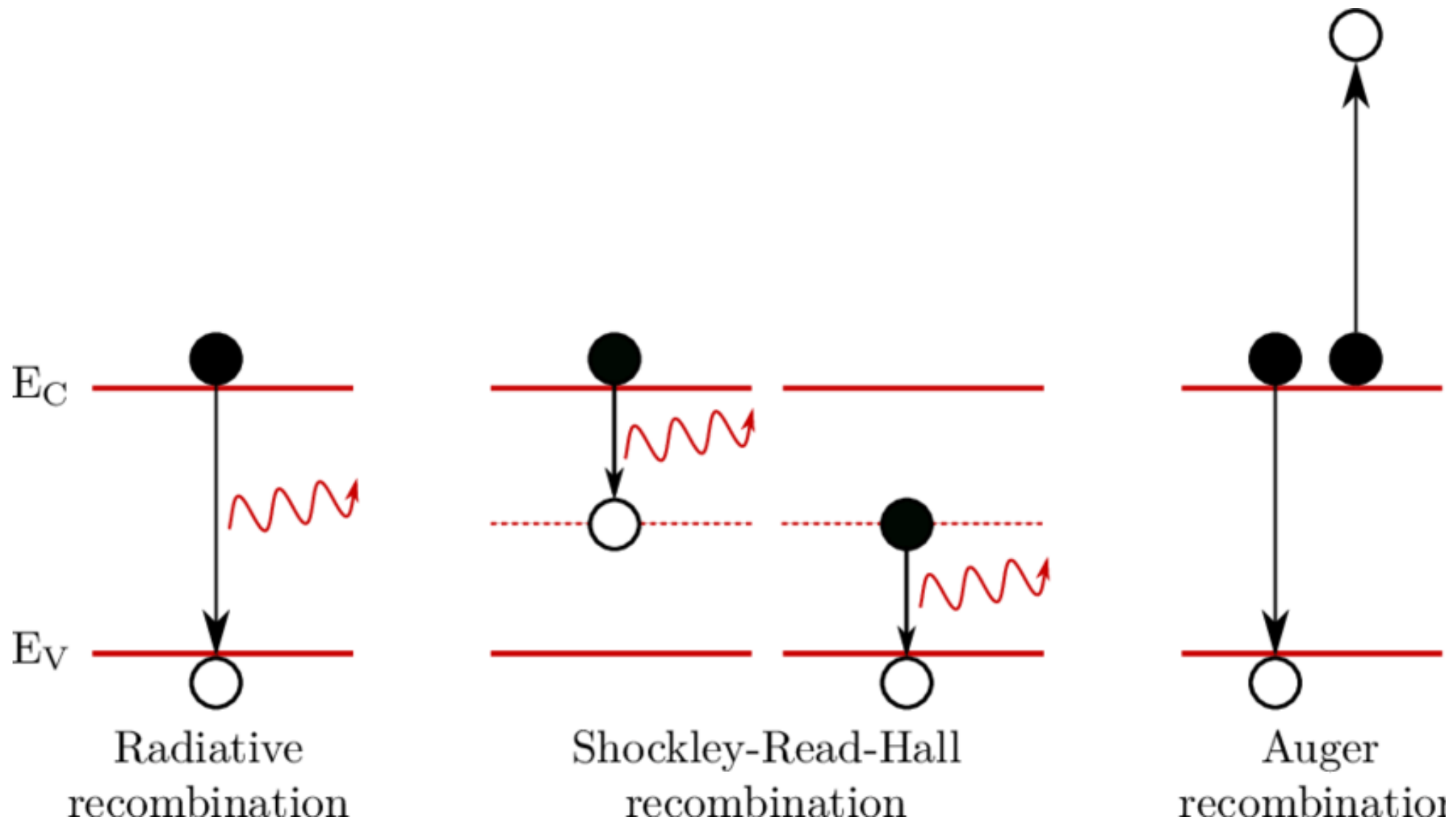
Outlook

- Studying impact of additional **variations in the doping profiles** on the cluster observables
- Comparison of simulation against **FastPix measurements** (analogue information available)
- TCAD+APSQ simulations for 65 nm process

A thousand thanks to Magdalena and Simon for their invaluable support and supervision for this work

Thank you for your attention

Back-up



In-pixel cluster size difference

High smearing

$$C_a = 2 \times 10^{-30}$$

Thrd = 170e

